

L Number	Hits	Search Text	DB	Time stamp
-	6217	inspect\$4 and (Electron adj microscop\$4)	USPAT; US-PGPUB;	2003/12/11 12:10
-	6615	inspect\$4 and (Electron adj microscop\$4)	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	4638	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	471	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and untreat\$3 and treat\$4	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	0	"09820143"	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	798	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 and treat\$4) or (expos\$3 and unexpos\$3) or (radiat\$3 and unradiat\$3))	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	640	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 same treat\$4) or (expos\$3 same unexpos\$3) or (radiat\$3 same unradiat\$3))	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	169	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 same treat\$4) or (expos\$3 same unexpos\$3) or (radiat\$3 same unradiat\$3))) and photoresist\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	24	okoroanyanwu.in.	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	181	singh-bhanwar.in.	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	0	acheta-aldden.in.	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:10
-	725	layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	543	(layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	473	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	96	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5) and inspec\$5	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	279838	inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	11801	(inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11

-	766	((inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$) and ((enclos\$3 or encapsulat\$3) near4 (surface or layer))	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	52	((inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$) and ((enclos\$3 or encapsulat\$3) near4 (surface or layer))) and photoresist	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	567	(shell or (cross adj link\$4)) and (barrier or trap\$4) and layer and outgas\$4	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	929	inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam	USPAT; US-PGPUB	2003/12/11 12:11
-	211	(inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam) and ((treat\$4 or transform\$5) same surface)	USPAT; US-PGPUB	2003/12/11 12:11
-	15	(inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam) and ((treat\$4 or transform\$5) same surface same ("SEM" or microscop\$2) same inspect\$4)	USPAT; US-PGPUB	2003/12/11 12:11
-	794	photoresist\$4 same (bubble or shell)	USPAT; US-PGPUB	2003/12/11 12:11
-	120	(photoresist\$4 same (bubble or shell)) and electron and microscop\$2	USPAT; US-PGPUB	2003/12/11 12:11
-	2240	250/310	USPAT; US-PGPUB	2003/12/11 12:11
-	1714	250/311	USPAT; US-PGPUB	2003/12/11 12:11
-	2553	250/306	USPAT; US-PGPUB	2003/12/11 12:11
-	2158	250/307	USPAT; US-PGPUB	2003/12/11 12:11
-	426	(250/310 or 250/311 or 250/306 or 250/307) and photoresist\$4	USPAT; US-PGPUB	2003/12/11 12:11
-	368	((250/310 or 250/311 or 250/306 or 250/307) and photoresist\$4) and layer	USPAT; US-PGPUB	2003/12/11 12:11
-	95	((250/310 or 250/311 or 250/306 or 250/307) and photoresist\$4) and layer) and electron and inspect\$4	USPAT; US-PGPUB	2003/12/11 12:11
-	149	430/16	USPAT	2003/12/11 12:11
-	515	430/23	USPAT	2003/12/11 12:11
-	2097	430/30	USPAT	2003/12/11 12:11
-	1984	430/296	USPAT	2003/12/11 12:11
-	3175	430/311	USPAT	2003/12/11 12:11
-	1079	438/623	USPAT	2003/12/11 12:11
-	653	438/701	USPAT	2003/12/11 12:11
-	897	438/725	USPAT	2003/12/11 12:11
-	5535	(430/16 or 430/23 or 430/30 or 430/296 or 430/311 or 438/623 or 438/701 or 438/725) and photoresist\$4	USPAT; US-PGPUB	2003/12/11 12:11
-	5119	((430/16 or 430/23 or 430/30 or 430/296 or 430/311 or 438/623 or 438/701 or 438/725) and photoresist\$4) and layer	USPAT; US-PGPUB	2003/12/11 12:11

-	417	((430/16 or 430/23 or 430/30 or 430/296 or 430/311 or 438/623 or 438/701 or 438/725) and photoresist\$4) and layer) and electron and inspect\$4	USPAT; US-PGPUB	2003/12/11 12:11
-	198	((430/16 or 430/23 or 430/30 or 430/296 or 430/311 or 438/623 or 438/701 or 438/725) and photoresist\$4) and layer) and electron and inspect\$4) and microscop\$2	USPAT; US-PGPUB	2003/12/11 12:11
-	57	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and untreat\$3 and treat\$4) and photoresist\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	26	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 same treat\$4) or (expos\$3 same unexpos\$3) or (radiat\$3 same unradiat\$3)) and photoresist\$3) and flood\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	37	(okoroanyanwu.in. or singh-bhanwar.in.) and (Electron adj microscop\$4)	USPAT; US-PGPUB	2003/12/11 12:11
-	1	((okoroanyanwu.in. or singh-bhanwar.in.) and (Electron adj microscop\$4)) and untreat\$3	USPAT; US-PGPUB	2003/12/11 12:11
-	24	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5) and shell	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:11
-	45	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5) and inspec\$5) and enclos\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:12
-	59	((inspect\$4 and electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$) and ((enclos\$3 or encapsulat\$3) near4 (surface or layer))) and photoresist\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:12
-	53	((shell or (cross adj link\$4)) and (barrier or trap\$4) and layer and outgas\$4) and photoresist\$4	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:12
-	2	5330881.pn.	USPAT; US-PGPUB; EPO; DERWENT	2003/12/11 12:12
-	15	((inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam) and ((treat\$4 or transform\$5) same surface)) and ((treat\$4 or transform\$5) same surface same ("SEM" or microscop\$2) same inspect\$4)	USPAT; US-PGPUB	2003/12/11 12:12
-	39	((photoresist\$4 same (bubble or shell)) and electron and microscop\$2) and (flood\$3 or inspect\$4)	USPAT; US-PGPUB	2003/12/11 12:12
-	91	((250/310 or 250/311 or 250/306 or 250/307) and photoresist\$4) and layer) and electron and inspect\$4) and microscop\$2	USPAT; US-PGPUB	2003/12/11 12:12
-	11	(US-6143666-\$ or US-5783366-\$ or US-6444381-\$ or US-5510216-\$ or US-6420702-\$ or US-6589709-\$ or US-6358670-\$ or US-5928821-\$ or US-5242864-\$ or US-6121130-\$ or US-5747803-\$).did.	USPAT	2003/12/11 12:12
-	17	((430/16 or 430/23 or 430/30 or 430/296 or 430/311 or 438/623 or 438/701 or 438/725) and photoresist\$4) and layer) and electron and inspect\$4) and microscop\$2) and flood\$3	USPAT; US-PGPUB	2003/12/11 12:12